

FIGURE 1a

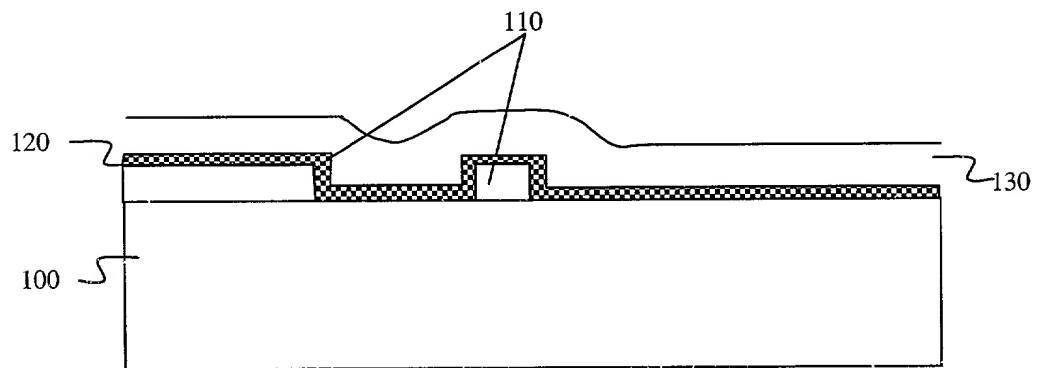


FIGURE 1b

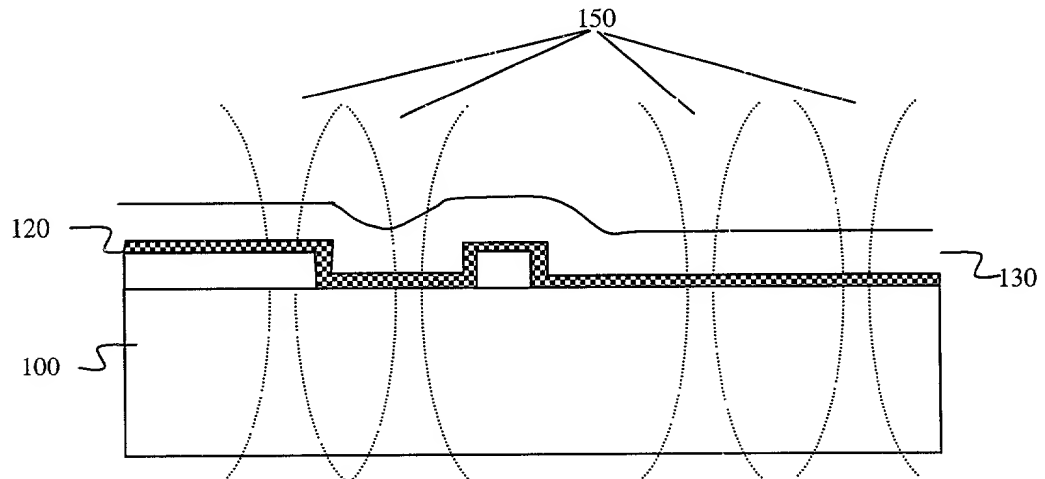


FIGURE 1c

Figure 1: Prior Art Lithography Processing

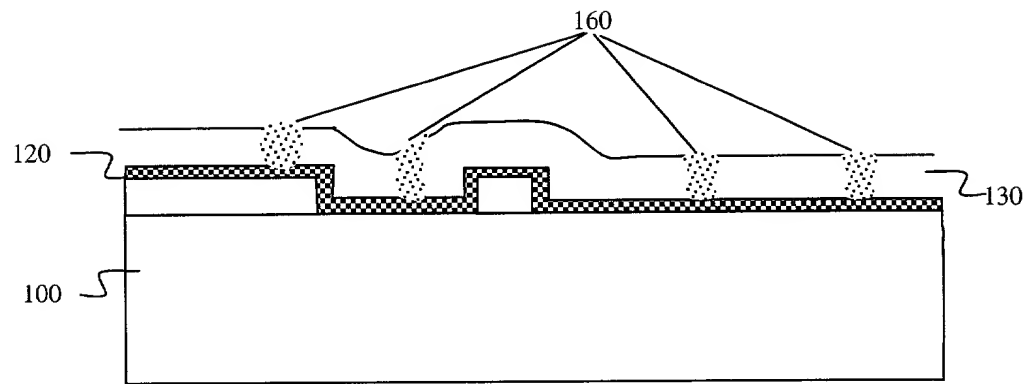


FIGURE 1d

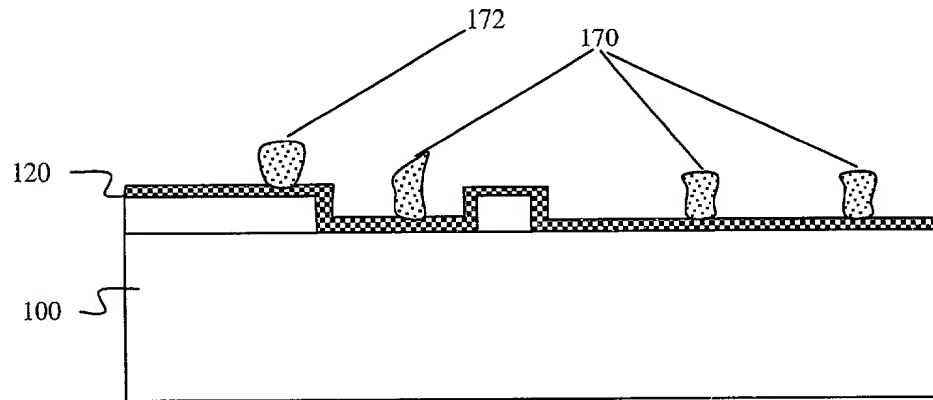


FIGURE 1e

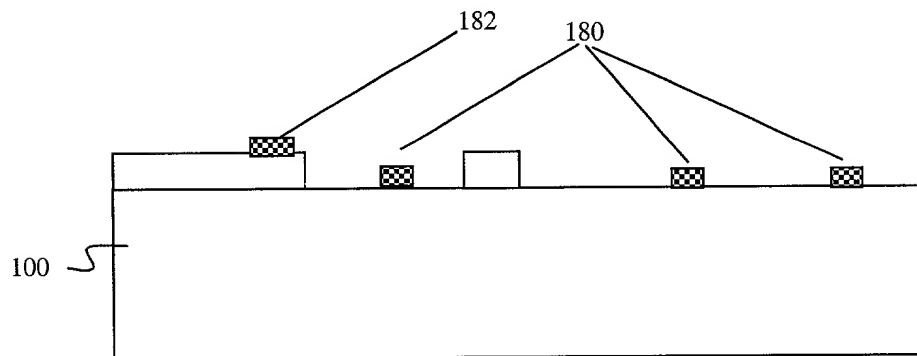


FIGURE 1f

Figure 1: Prior Art Lithography Processing

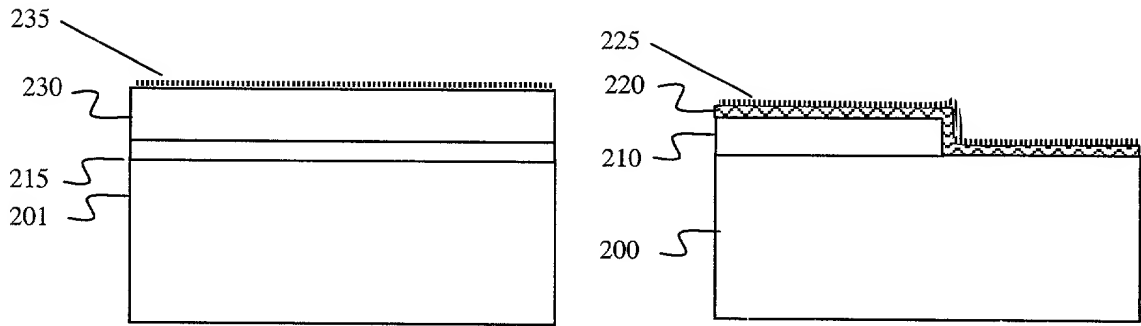


FIGURE 2a

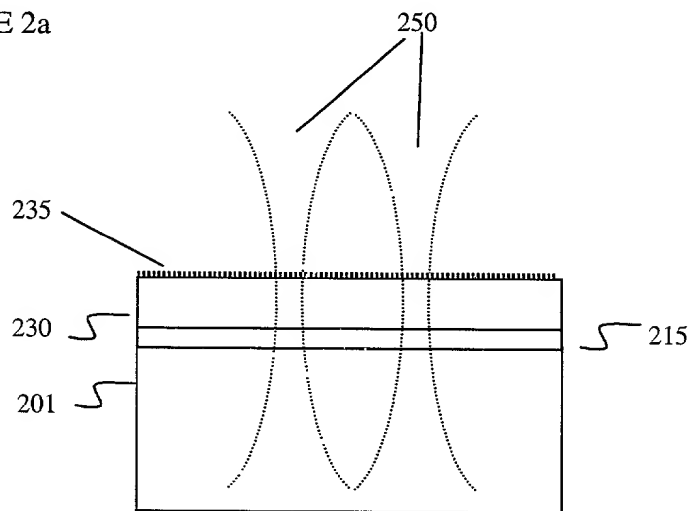


FIGURE 2b

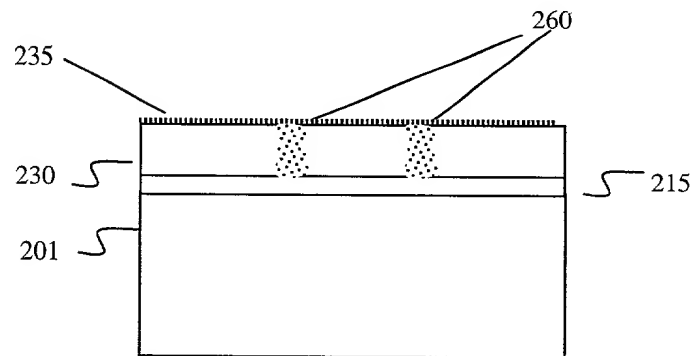


FIGURE 2c

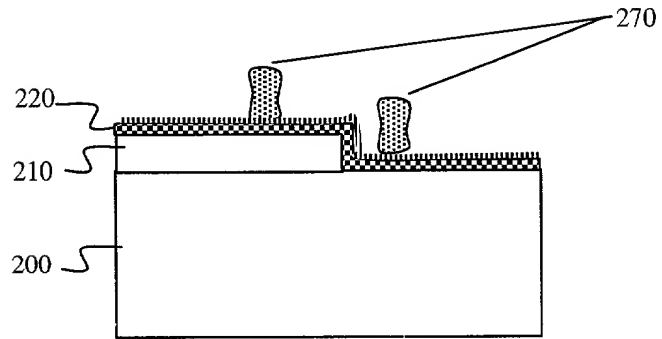


FIGURE 3c

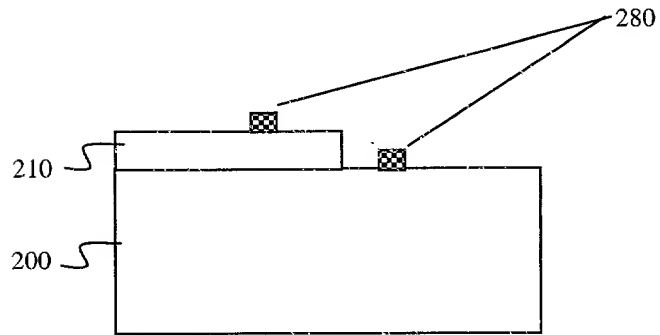


FIGURE 3d

DRAWINGS (Draft)

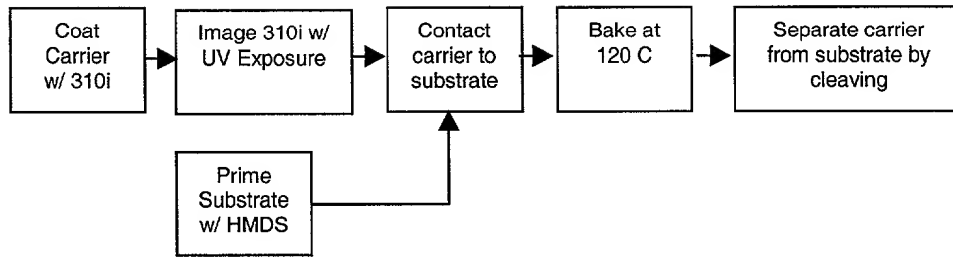


Figure 4a

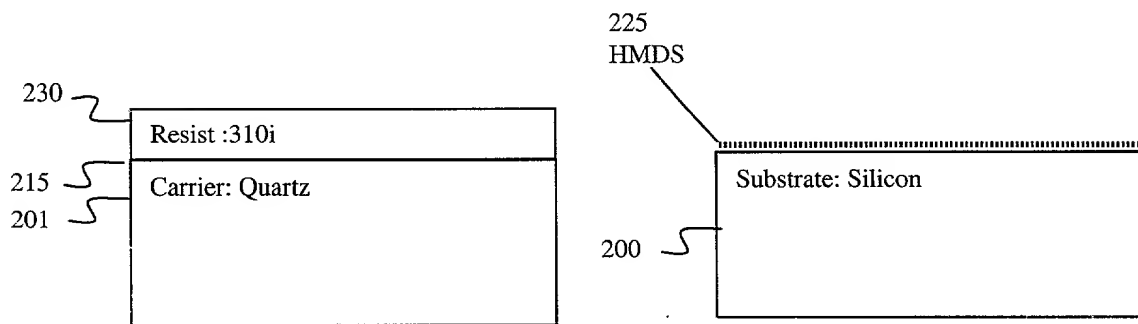


Figure 4b

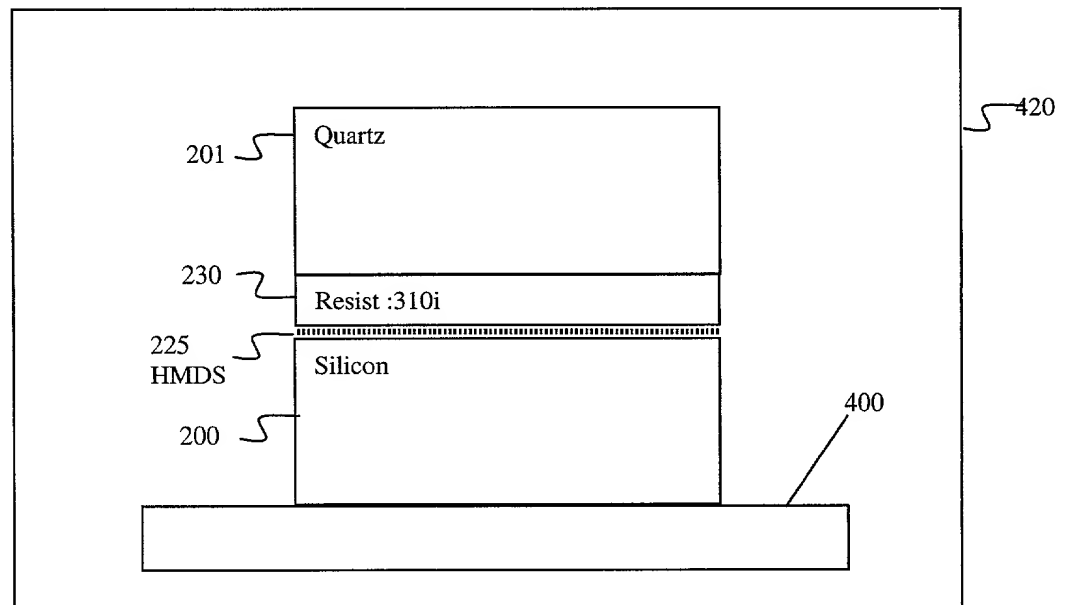


Figure 4c

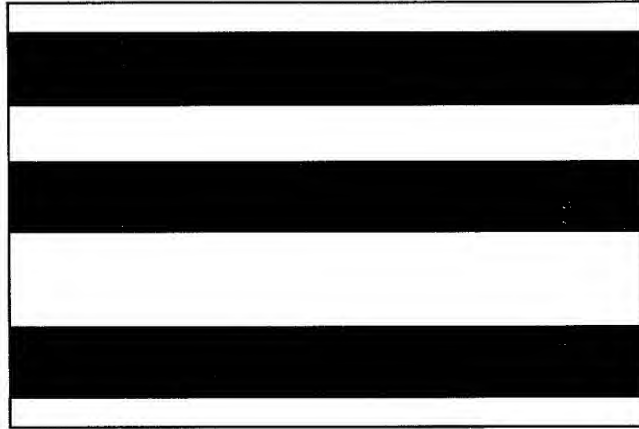


FIGURE 5: Mask Photo

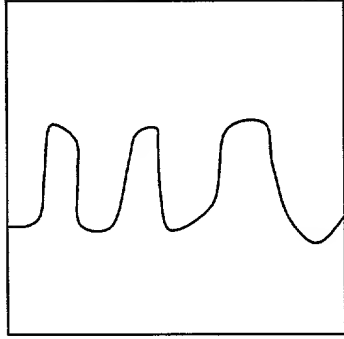


FIGURE 6a: Fringes before transfer

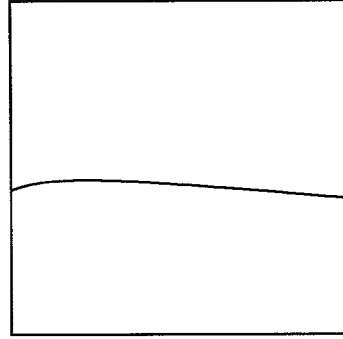


FIGURE 6b: Fringes after transfer

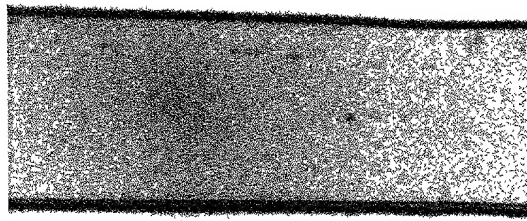


FIGURE 7: Developed Photoresist

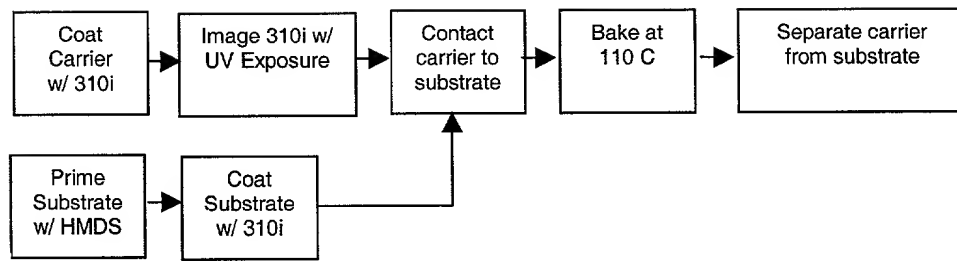


Figure 8a

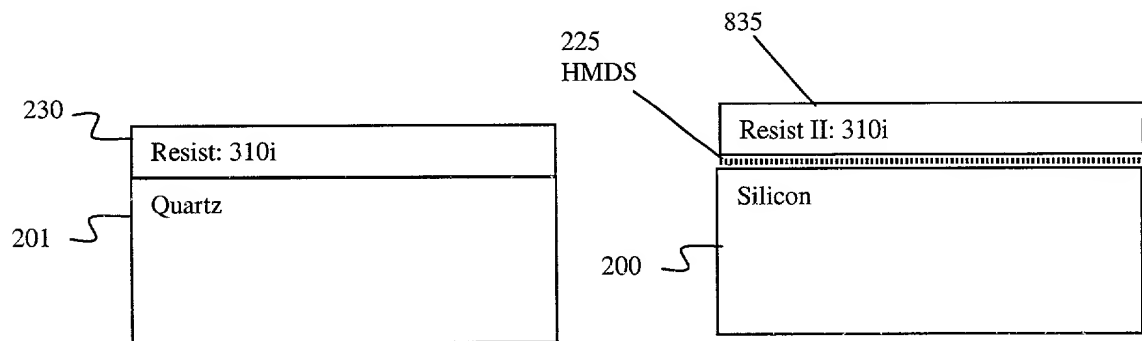


Figure 8b.

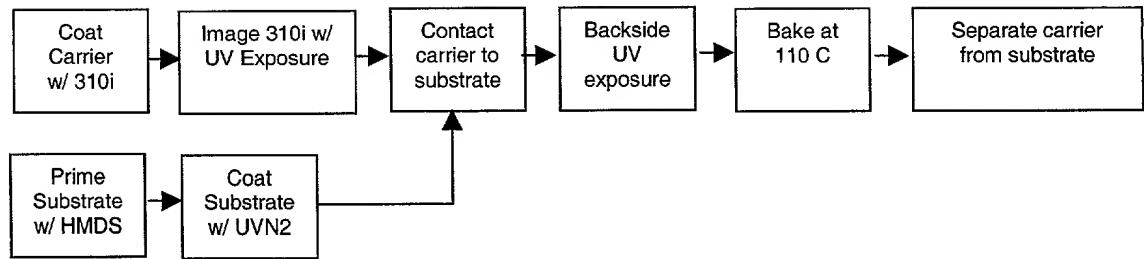


Figure 9a

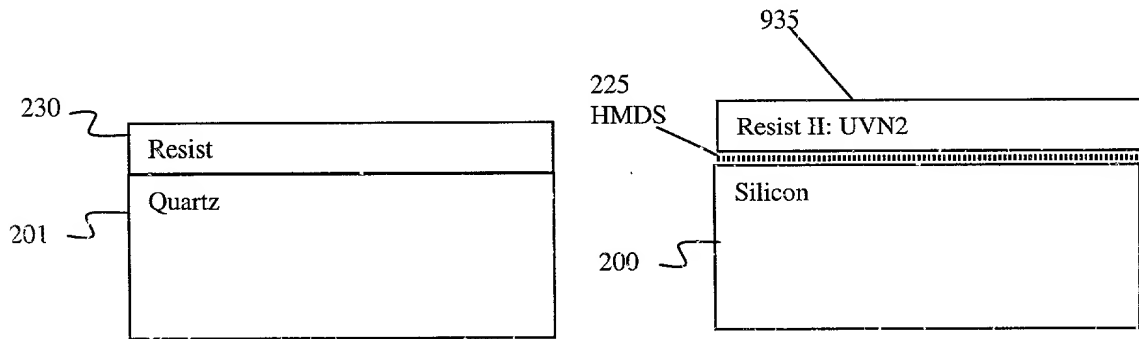


Figure 9b

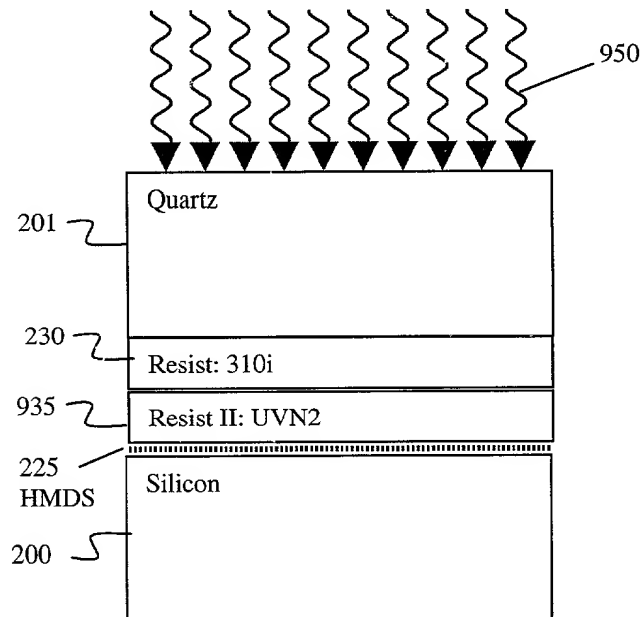


Figure 9c

DRAWINGS (Draft)

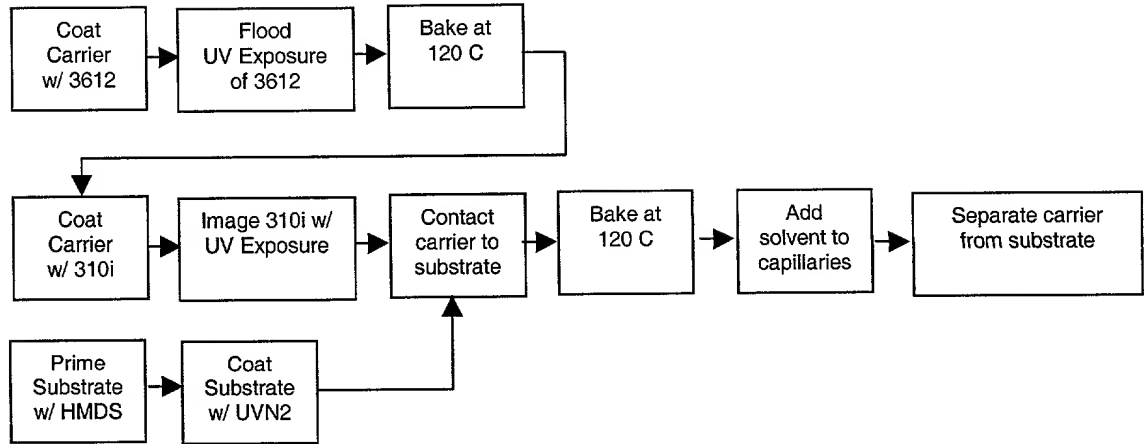


Figure 10a

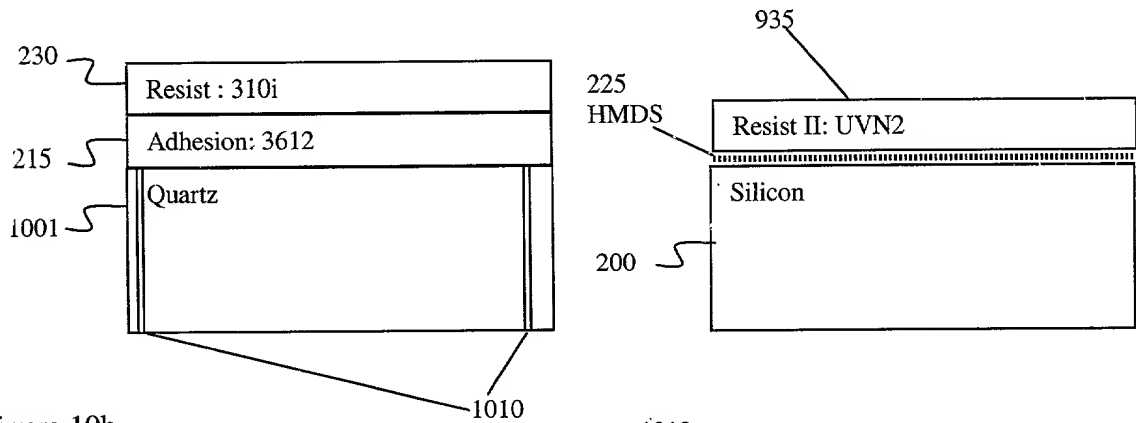


Figure 10b

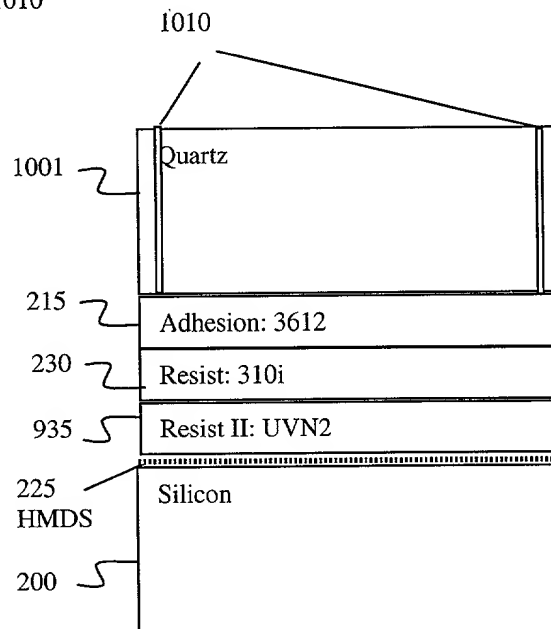


Figure 10c